

Notice of References Cited		Application/Control No. 10/519,650	Applicant(s)/Patent Under Reexamination FRENCH ET AL.	
		Examiner DAVID GOODWIN	Art Unit 2818	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-2001/0051302	12-2001	DOVE et al.	430/5
*	B	US-5,882,827	03-1999	Nakao, Shuji	430/5
*	C	US-2002/0061452	05-2002	Nozawa et al.	430/5
	D	US-			
	E	US-			
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Smith "Attenuated phase shift mask materials for 248 and 193 nm lithography" J.Vac. Sci. Technol. B Volume 14, issue 6, pp 3719-3723 (November 1996)
	V	
	W	
	X	

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.